L Number	Hits	Search Text	DB	Time stamp
2	10	KUBACKI-RONALD-Min.	USPAT;	2004/03/11 14:08
		KUBACKI-RONALD-MICHAELin.	US-PGPUB;	
		KUBACKI-R-Min.	EPO; JPO;	
3	2	/#.C.41.C.02.0.W.\ DN	DERWENT	
3	2	("6416938").PN.	USPAT;	2004/03/11 14:08
			US-PGPUB;	-
			EPO; JPO;	
5	261838	photosensitive photo-sensitive photo adj	DERWENT	2004/02/11 14-15
J	201030	sensitive   sensitive   sensitive   sensitive	USPAT; US-PGPUB;	2004/03/11 14:15
		SCHOLLIVE	EPO; JPO;	
			DERWENT	
6	3362	silicon adj hydride	USPAT;	2004/03/11 15:07
			US-PGPUB;	2001,03,11 13.0,
		·	EPO; JPO;	
			DERWENT	
7	40167	monosilane sih4 "sih.sub.4" disilane si2h6	USPAT;	2004/03/11 14:16
		"si.sub.2 h.sub.6" dichlorosilane sih2 cl2	US-PGPUB;	
		"sih.sub.2 cl.sub.2"	EPO; JPO;	
			DERWENT	
8	791792	ethylene c2h4 "c.sub.2 h.sub.4" methane	USPAT;	2004/03/11 14:17
		ch4 "ch.sub.4" ethane c2h6 "c.sub.2	US-PGPUB;	
		h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5	EPO; JPO;	
		ch.sub.3"	DERWENT	
9	6601	si-h si-si	USPAT;	2004/03/11 15:53
		·	US-PGPUB;	
			EPO; JPO;	
10	204466	<i>European</i>	DERWENT	
10	204466	fragment	USPAT;	2004/03/11 14:17
			US-PGPUB;	
			EPO; JPO;	
11	44644	(oragnic polymer\$3) near2 matrix	DERWENT	2004/02/11 14 10
11	74044	(Oragine polymerss) hearz matrix	USPAT; US-PGPUB;	2004/03/11 14:18
		·	EPO; JPO;	
			DERWENT	
12	250570	(silicon si) near4 (oxide dioxide oxidate	USPAT;	2004/03/11 14:21
		oxidation oxidiated oxidating)	US-PGPUB;	2004/03/11 14.21
		J,	EPO; JPO;	
			DERWENT	
13	3908	430/9,322,324.ccls. 427/487,488,489.ccls.	USPAT;	2004/03/11 14:22
		428/420.ccls. 216/62.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
4	. 67	selective with wetting with material	USPAT;	2004/03/11 14:27
			US-PGPUB;	
			EPO; JPO;	
14	۾ ا	anliation was a second	DERWENT	
14	, 3	selective near2 wetting near2 material	USPAT;	2004/03/11 14:28
. [	İ	•	US-PGPUB;	
1			EPO; JPO;	
15	5963	watting page matarial	DERWENT	0004/00/44
10	2362	wetting near2 material	USPAT;	2004/03/11 14:28
			US-PGPUB;	
ļ			EPO; JPO;	
17	19	((selective with wetting with material )	DERWENT	2004/02/11 14:00
	19	(wetting near2 material )) same	USPAT;	2004/03/11 14:28
		(photosensitive photo-sensitive photo adj	US-PGPUB;	
		sensitive)	EPO; JPO; DERWENT	
16	14	((selective with wetting with material )	USPAT;	2004/03/11 14:54
		(wetting near2 material )) with	US-PGPUB;	2003/03/11 14:34
		(photosensitive photo-sensitive photo adj	EPO; JPO;	
*		sensitive)	DERWENT	
			>	

18	5	<pre>(((selective with wetting with material )   (wetting near2 material )) same   (photosensitive photo-sensitive photo adj   sensitive )) not (((selective with wetting   with material ) (wetting near2 material ))   with (photosensitive photo-sensitive photo   adj sensitive ))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 14:54
19	26108		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:00
20	68	<pre>(photosensitive photo-sensitive photo adj sensitive ) with (plasma-deposit\$5 plasma near2 deposit\$5 )</pre>	USPAT; US-PGPUB; EPO; JPO;	2004/03/11 15:01
21	118	(photosensitive photo-sensitive photo adj sensitive) same ((silicon adj hydride) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2")) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3")	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:11
23	6	(430/9,322,324.ccls. 427/487,488,489.ccls. 428/420.ccls. 216/62.ccls.) and ((selective with wetting with material) ((photosensitive photo-sensitive photo adj sensitive) with (plasma-deposit\$5 plasma near2 deposit\$5)) ((photosensitive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:10
	·	photo-sensitive photo adj sensitive ) same ((silicon adj hydride ) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6" dichlorosilane sih2 cl2 "sih.sub.2 cl.sub.2" )) same (ethylene c2h4 "c.sub.2 h.sub.4" methane ch4 "ch.sub.4" ethane c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3" )))		
25	1		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:11
24	40	, , , , , , , , , , , , , , , , , , , ,	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:13
26	2718816	oxidating)) organo-silicon organosilicon silicon si	USPAT;	2004/03/11 15:14
		organic	US-PGPUB; EPO; JPO;	2501,03,11 13.14
27	30	((photosensitive photo-sensitive photo adj sensitive) with (plasma-deposit\$5 plasma near2 deposit\$5)) with (organo-silicon organosilicon silicon si organic)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/11 15:16

			7	
28	100617		USPAT;	2004/03/11 15:20
		light)	US-PGPUB;	
			EPO; JPO; DERWENT	
29	82	((photosensitive photo-sensitive photo adj	USPAT;	2004/03/11 15:21
23	02	sensitive) (sensitive near (photo	US-PGPUB;	2004/03/11 13.21
		radiation energy light))) with	EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5)	DERWENT	
30	13027	si-contain\$3 silicon-contain\$3	USPAT;	2004/03/11 15:22
			US-PGPUB;	
			EPO; JPO;	
21	2.5		DERWENT	0004/00/44 45 00
31	35	1 , , , ,	USPAT;	2004/03/11 15:22
		adj sensitive ) (sensitive near (photo radiation energy light))) with	US-PGPUB; EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5	DERWENT	}
		)) with ((organo-silicon organosilicon	BEIMBINI	
		silicon si organic) (si-contain\$3		
		silicon-contain\$3))		
33	30	1 ( ( ( I I I I I I I I I I I I I	USPAT;	2004/03/11 15:30
		adj sensitive ) (sensitive near (photo	US-PGPUB;	
		radiation energy light))) with	EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5	DERWENT	
		)) with ((organo-silicon organosilicon silicon si organic) (si-contain\$3		
		silicon-contain\$3))) and ((monosilane sih4		
		"sih.sub.4" disilane si2h6 "si.sub.2		
		h.sub.6" dichlorosilane sih2 cl2		
		"sih.sub.2 cl.sub.2" ) (ethylene c2h4		
1		"c.sub.2 h.sub.4" methane ch4 "ch.sub.4"		
		ethane c2h6 "c.sub.2 h.sub.6" toluene		
		c6h5ch3 "c.sub.6 h.sub.5 ch.sub.3") (si-h		
		si-si) fragment ((oragnic polymer\$3) near2 matrix) ((silicon si) near4 (oxide dioxide		
		oxidate oxidation oxidiated oxidating)))		
35	10	((((photosensitive photo-sensitive photo	USPAT;	2004/03/11 15:31
		adj sensitive ) (sensitive near (photo	US-PGPUB;	2001/03/11 13:31
		radiation energy light))) with	EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5	DERWENT	
		)) with ((organo-silicon organosilicon		
		silicon si organic) (si-contain\$3		
		silicon-contain\$3))) and ((((silicon adj		
		hydride ) (monosilane sih4 "sih.sub.4" disilane si2h6 "si.sub.2 h.sub.6"		
		dichlorosilane sih2 cl2 "sih.sub.2		
		cl.sub.2" )) with (ethylene c2h4 "c.sub.2		,
		h.sub.4" methane ch4 "ch.sub.4" ethane		
		c2h6 "c.sub.2 h.sub.6" toluene c6h5ch3		
		"c.sub.6 h.sub.5 ch.sub.3" )))		
36	5	, , , , , , , , , , , ,	USPAT;	2004/03/11 15:37
		photo-sensitive photo adj sensitive )	US-PGPUB;	
		(sensitive near (photo radiation energy light))) with (plasma-deposit\$5 plasma	EPO; JPO;	
		near2 deposit\$5 )) with ((organo-silicon	DERWENT	
		organosilicon silicon si organic)		
		(si-contain\$3 silicon-contain\$3)))		
37	5	(si-h si-si) with fragment	USPAT;	2004/03/11 15:38
			US-PGPUB;	
	1.14		EPO; JPO;	
20			DERWENT	
38	6	, , , ( o	USPAT;	2004/03/11 15:49
		near2 matrix)	US-PGPUB;	
			EPO; JPO; DERWENT	
39	13	(si-h si-si) same ((oragnic polymer\$3)	USPAT;	2004/03/11 15:50
		near2 matrix)	US-PGPUB;	2001/03/11 13.30
		·	EPO; JPO;	
			DERWENT	

40	7	((si-h si-si) same ((oragnic polymer\$3)	USPAT;	2004/03/11 15:49
		near2 matrix)) not ((si-h si-si) with	US-PGPUB;	
		((oragnic polymer\$3) near2 matrix))	EPO; JPO;	
			DERWENT	
41	2178	(si-h si-si) same (organic polymer\$3	USPAT;	2004/03/11 15:54
		matrix)	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
42	4	(((photosensitive photo-sensitive photo	USPAT;	2004/03/11 15:54
		adj sensitive ) (sensitive near (photo	US-PGPUB;	
		radiation energy light))) with	EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5	DERWENT	
		)) and ((si-h si-si) same (organic		-
		polymer\$3 matrix))		
43	11265	sih sisi	USPAT;	2004/03/11 15:53
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
4 4	2201	(sih sisi) samé (organic polymer\$3 matrix)	USPAT;	2004/03/11 15:54
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
45	3	(((photosensitive photo-sensitive photo	USPAT;	2004/03/11 15:54
		adj sensitive ) (sensitive near (photo	US-PGPUB;	
		radiation energy light))) with	EPO; JPO;	
		(plasma-deposit\$5 plasma near2 deposit\$5	DERWENT	,
		)) and ((sih sisi) same (organic polymer\$3		
		matrix))	İ	